

<b>Notice of References Cited</b>	Application/Control No. 10/557,694		Applicant(s)/Patent Under Reexamination HADA ET AL.	
	Examiner Anca Eoff		Art Unit 1709	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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*	B	US-6,358,665	03-2002	Pawlowski et al.	430/270.1
*	C	US-2003/0049456	03-2003	Kawasato et al.	428/421
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	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

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	N					
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**NON-PATENT DOCUMENTS**

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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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